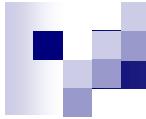


半导体 集成电路

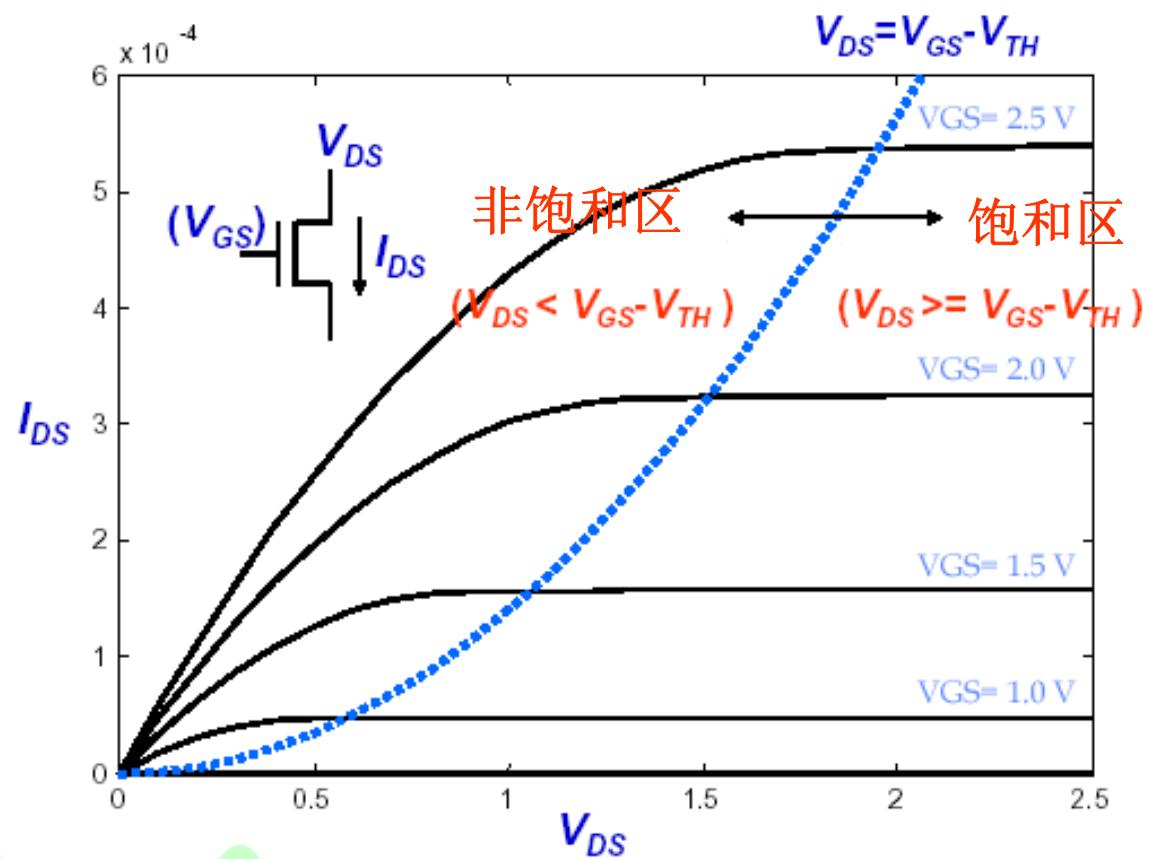
学校：西安理工大学
院系：自动化学院电子工程系
专业：电子、微电
时间：秋季学期



上节课内容要点

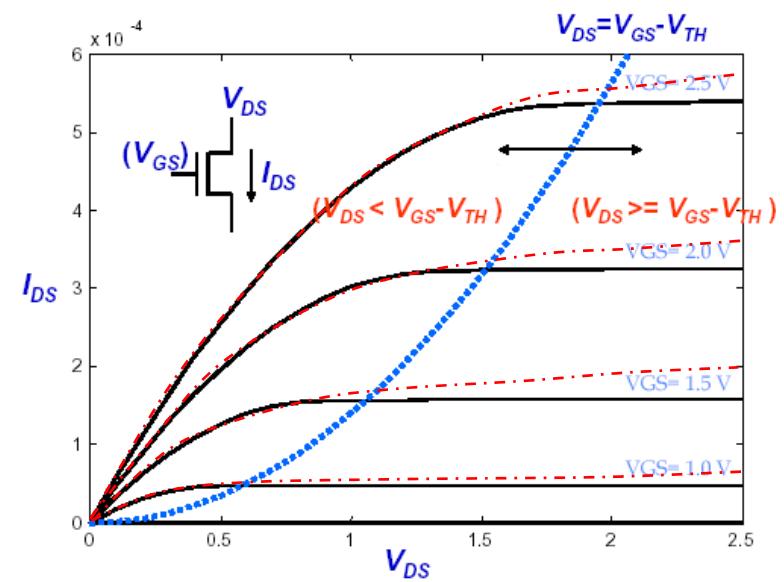
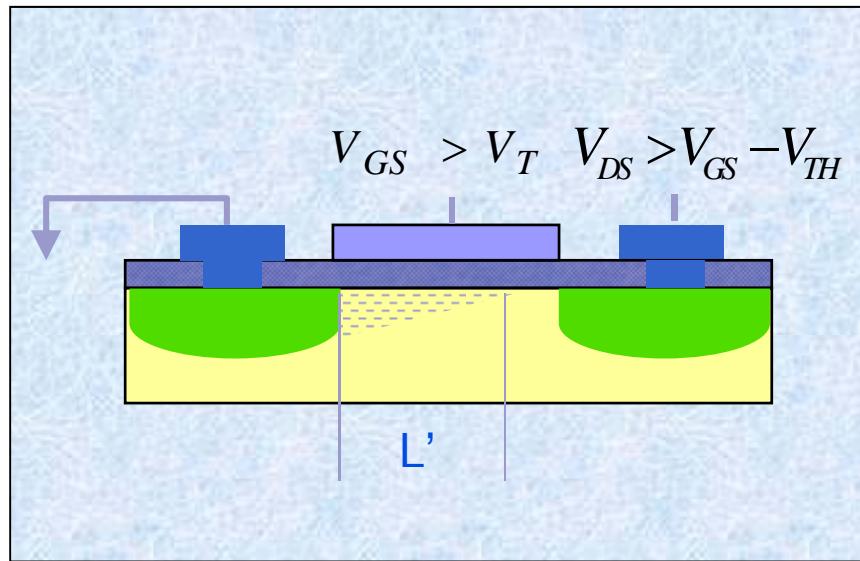
- MOS晶体管的小尺寸效应
- MOS晶体管的电容
- MOS晶体管的导通电阻

◆ 基本要求



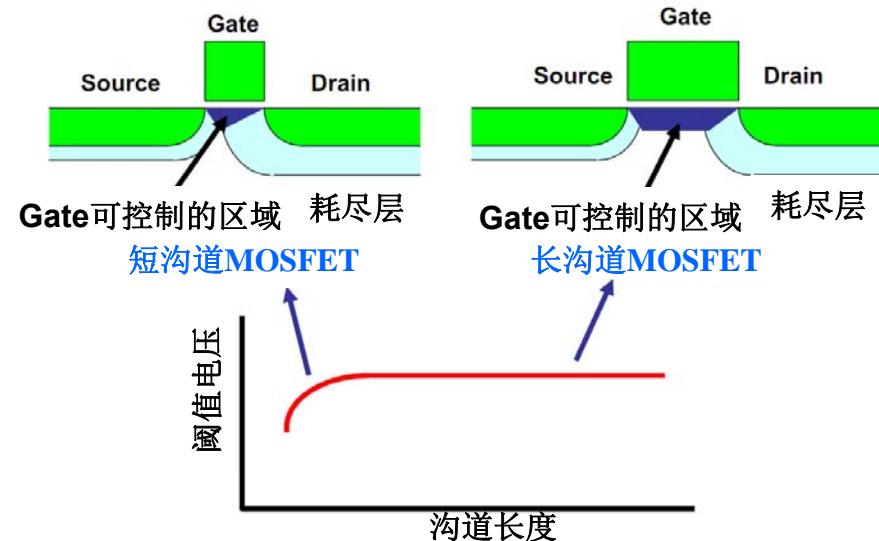
$$I_D \left\{ \begin{array}{l} I_{DS} = \mu C_{ox} \frac{W}{L} [(V_{GS} - V_{TH}) V_{DS} - \frac{1}{2} V_{DS}^2] \quad (0 < V_{DS} < V_{GS} - V_{TH}) \\ I_{DS} = \frac{1}{2} \mu C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2 \quad (V_{GS} - V_{TH} < V_{DS}) \end{array} \right.$$

◆ 沟道长度调制效应

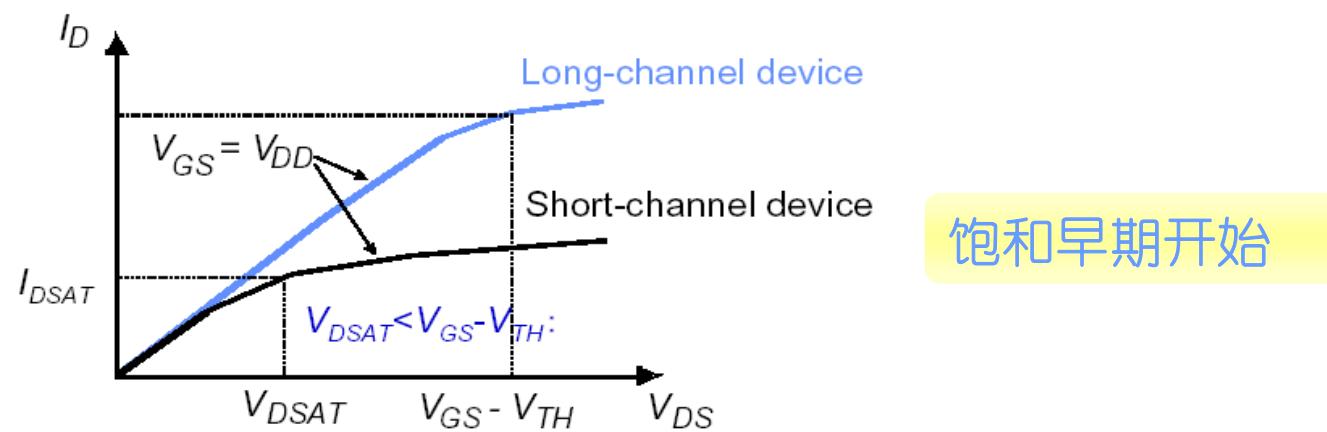


$$I_{DS} = \frac{1}{2} \mu C_{ox} \frac{W}{L'} (V_{GS} - V_{TH})^2$$

◆ 短沟道效应



◆ 速度早期饱和

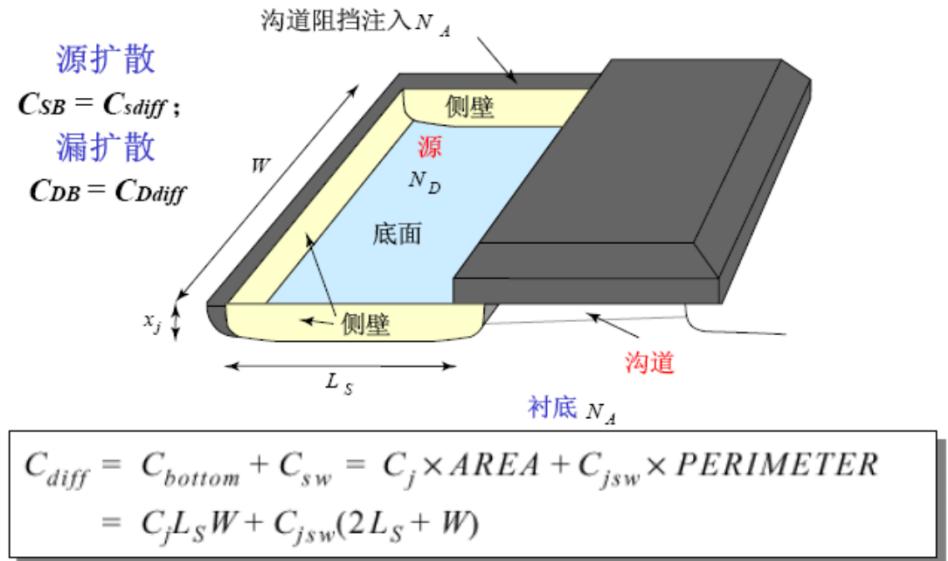
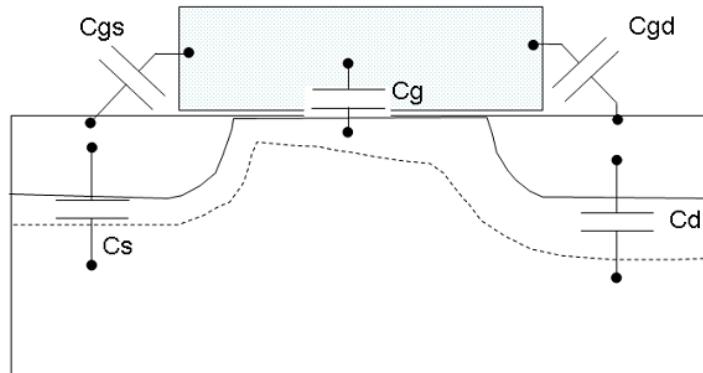


短沟道**MOSFET**的电流方程

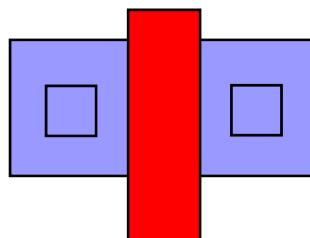
$$I_{DS} = K_n' \cdot \frac{W}{L} \left\{ (V_{GS} - V_{TH}) V_{min} - \frac{1}{2} V_{min}^2 \right\} (1 + \lambda V_{DS})$$

$$V_{min} = (V_{GS} - V_{TH}, V_{DS}, V_{DSAT})$$

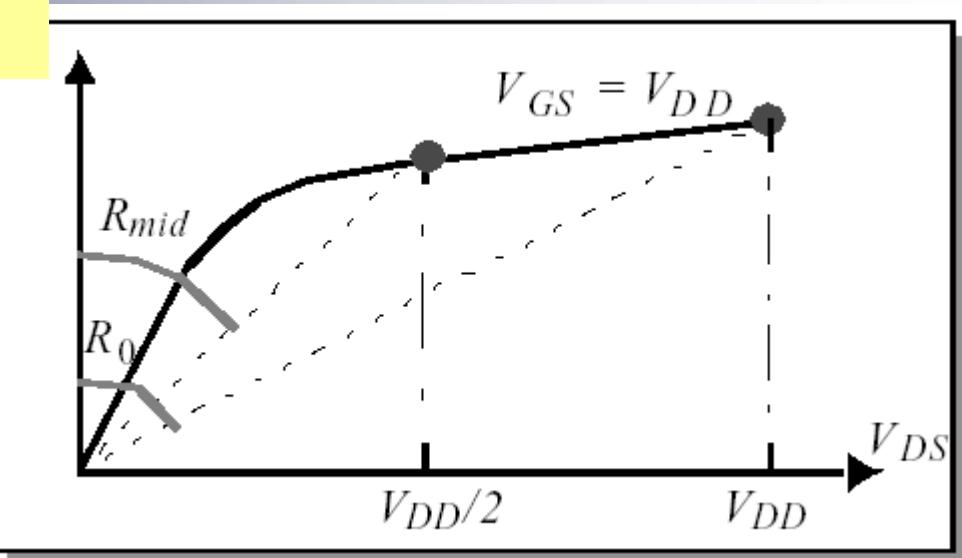
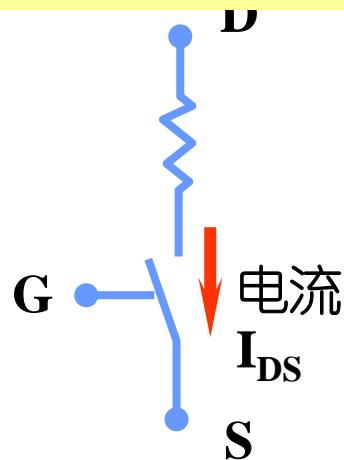
MOS晶体管的电容



栅极电容作为前一级的负载电容
漏源电容作为自身负载电容

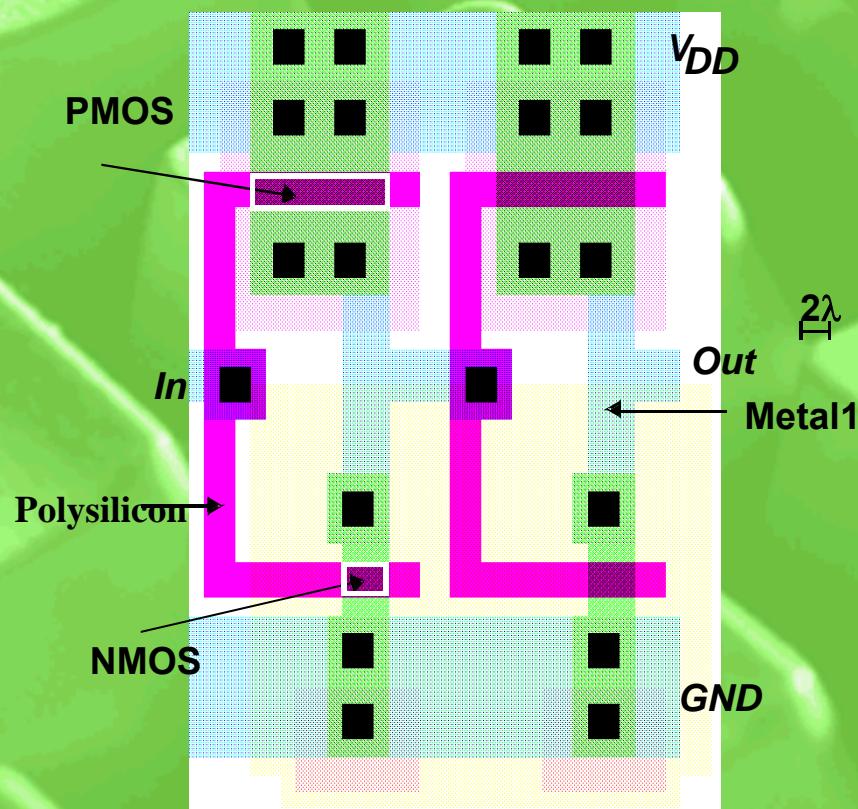


MOS晶体管的电阻

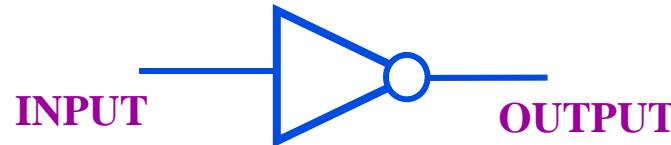


- 导通电阻是一个非线性电阻，与器件的工作状态有关，平均电阻一般取**0.75R₀**
 - 在非饱和区，导通电阻近似为线性电阻
- $$R_{on} \approx \frac{1}{\mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})} \text{ 即 } R_{on} = 1/g_m$$
- 导通电阻反比于**(W/L)**，W每增加一倍，电阻减小一半

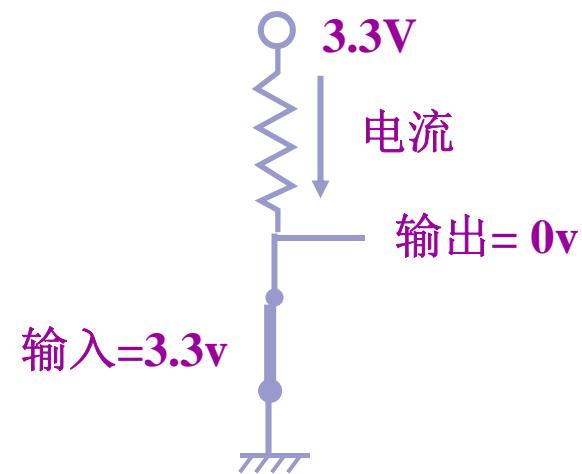
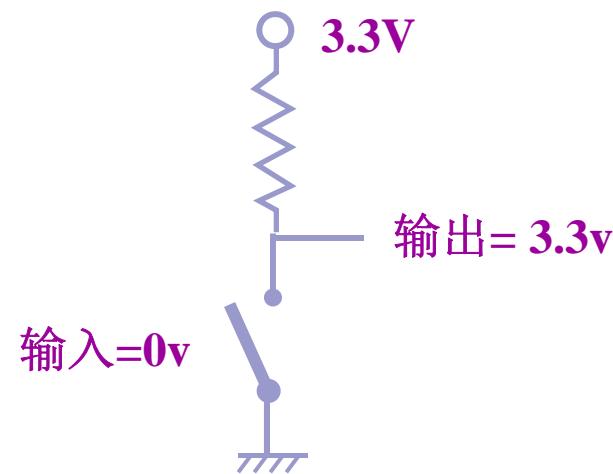
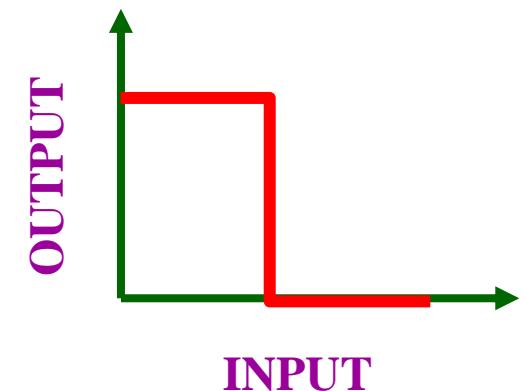
MOS反相器



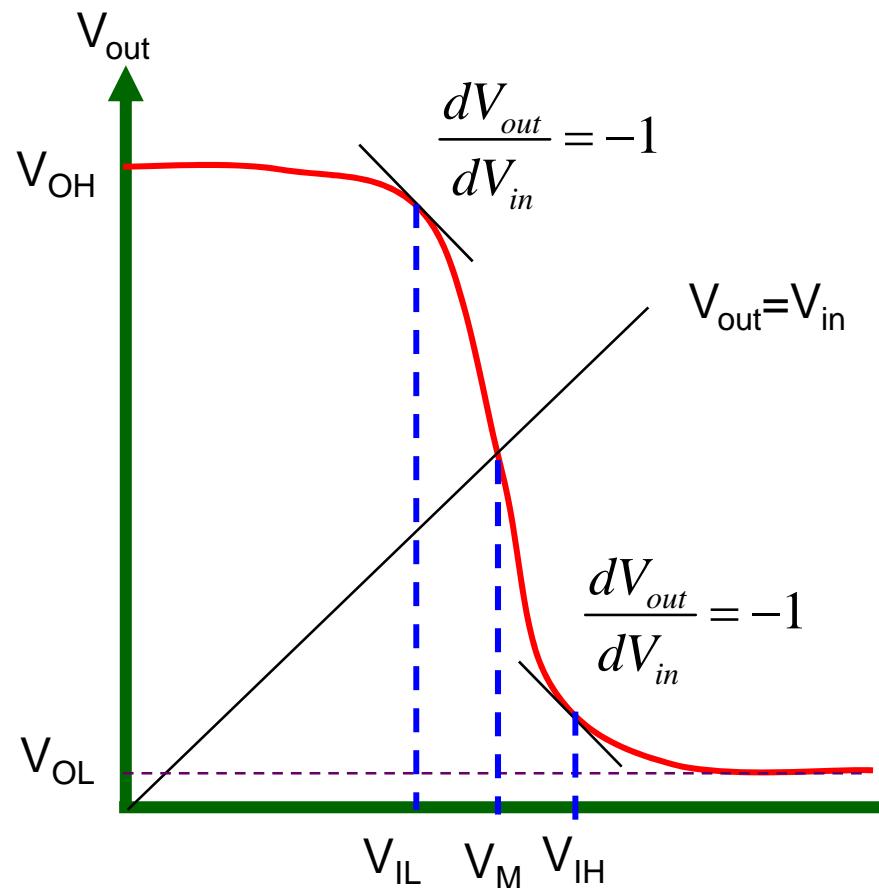
MOS反相器的静态特性



INPUT	OUTPUT
0	1
1	0



MOS反相器的电压传输特性



V_{OH} :输出电平为逻辑”1”时的最大输出电压

V_{OL} :输出电平为逻辑”0”时的最小输出电压

V_{IL} :仍能维持输出为逻辑”1”的最大输入电压

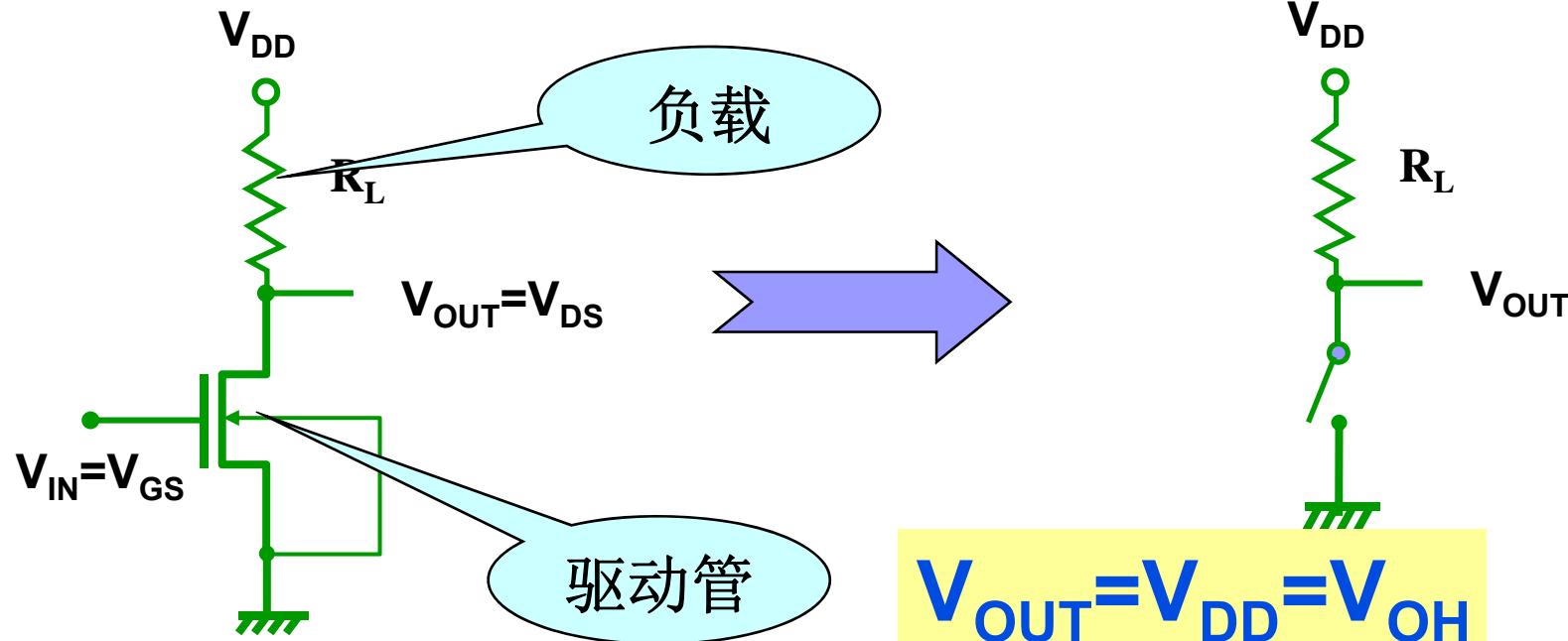
V_{IH} :仍能维持输出为逻辑”0”的最小输入电压

V_M :逻辑阈值，输入等于输出

电阻负载型反相器

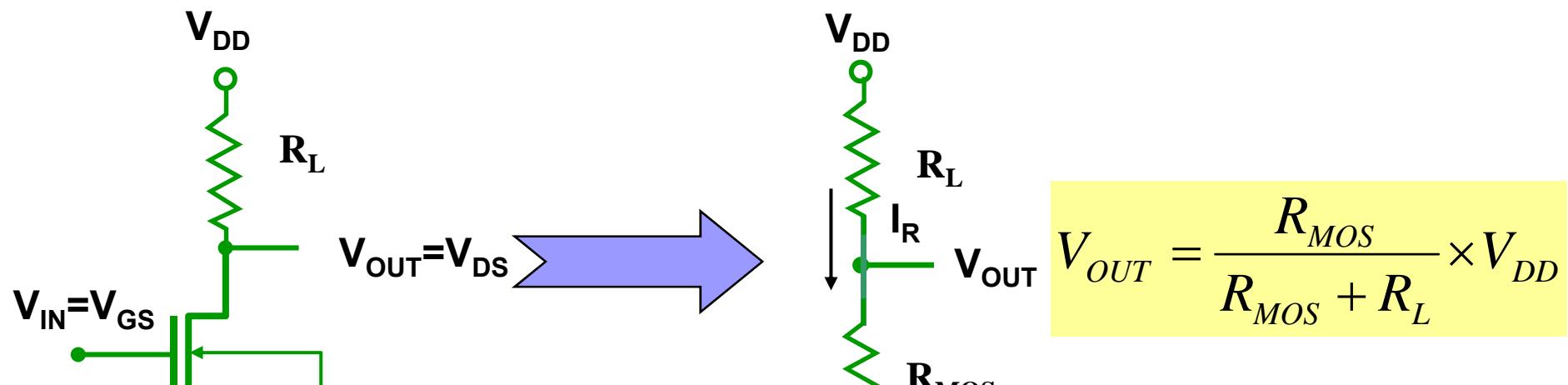
1. $V_{IN}=V_{LOW} \approx 0V$ 时

N管截止



2. $V_{IN}=V_{HIGH} \approx V_{DD}$ 时

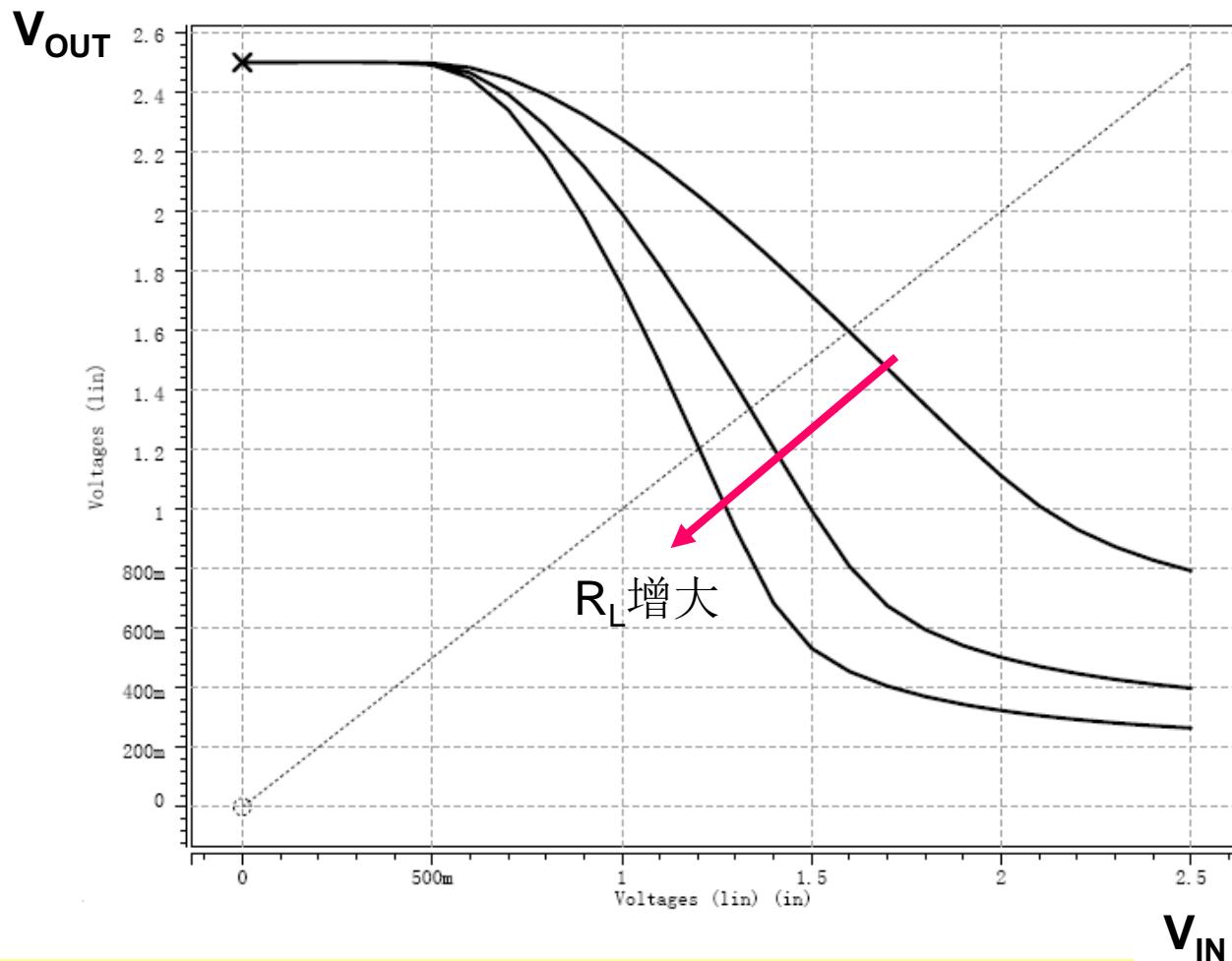
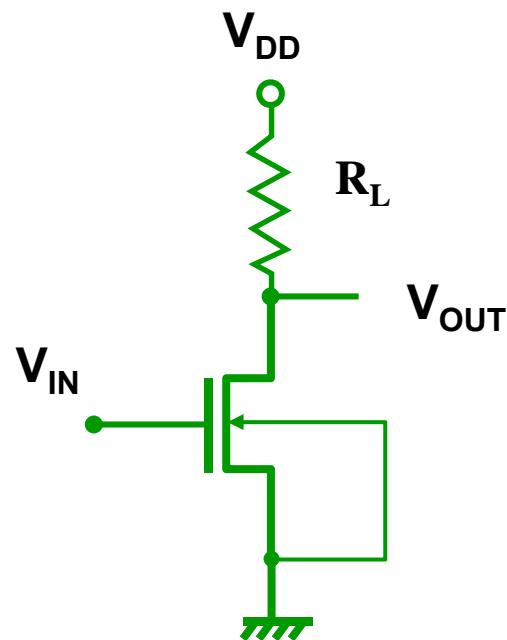
N管导通, 可将MOS等效为可变电阻 R_{MOS}



$$V_{OUT} = \frac{R_{MOS}}{R_{MOS} + R_L} \times V_{DD}$$

若 $R_L \gg R_{MOS}$ 则 $V_{OUT} \approx 0 = V_{OL}$

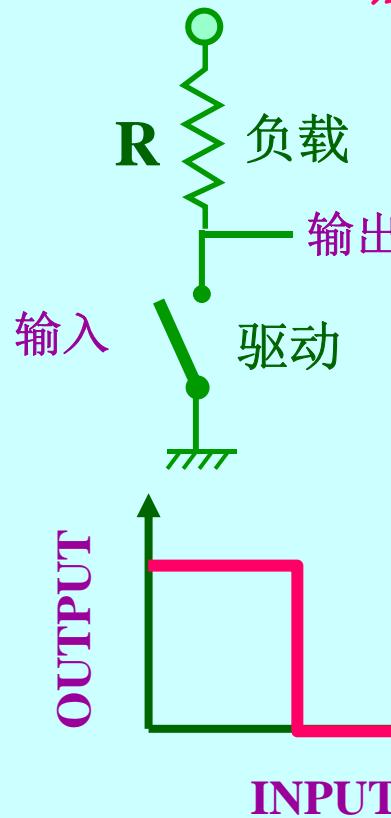
❖ 电阻负载型反相器电压传输特性



随着 R_L 的增大，输出低电平降低，逻辑阈值亦减小

反 相 器

反相器中电阻的实现



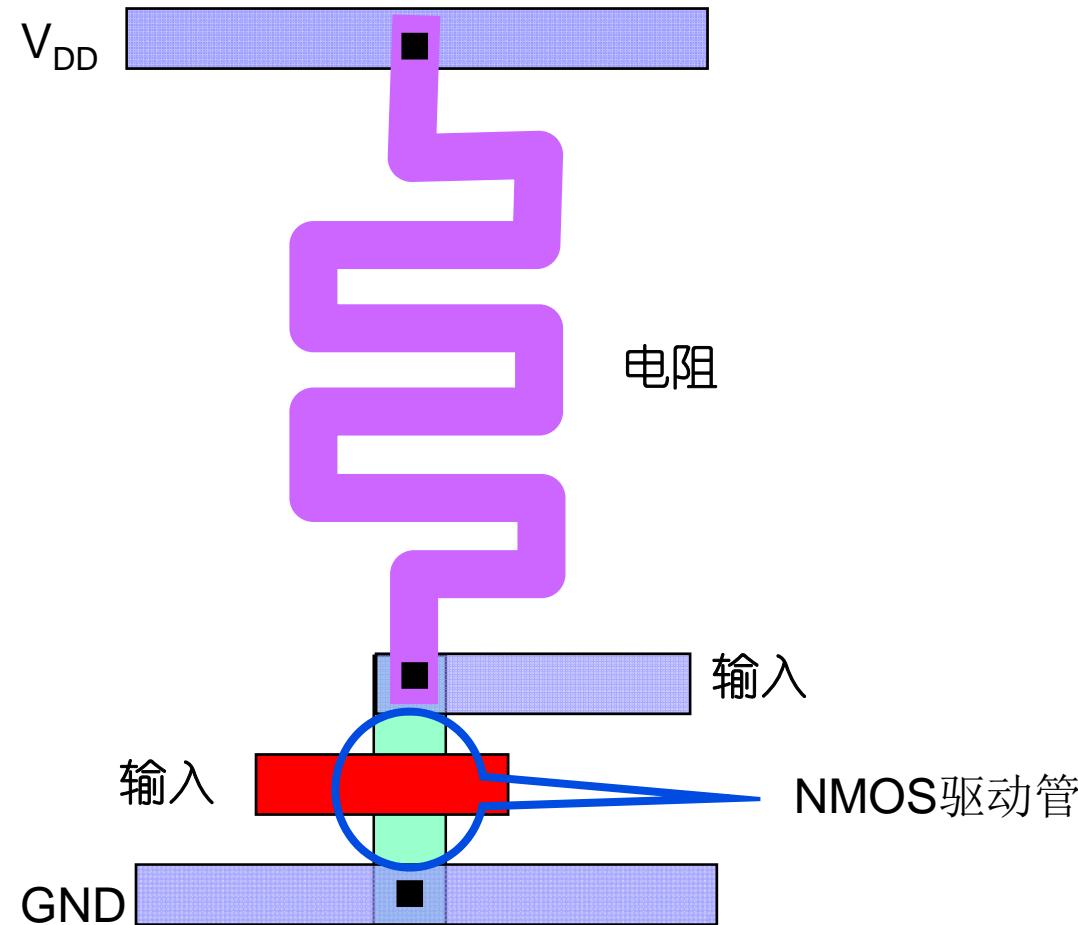
为了使反相器的传输特性好

在驱动管开关断开时，负载电阻相对于开关的电阻足够小

在驱动管开关闭合时，负载电阻相对于开关的电阻足够大

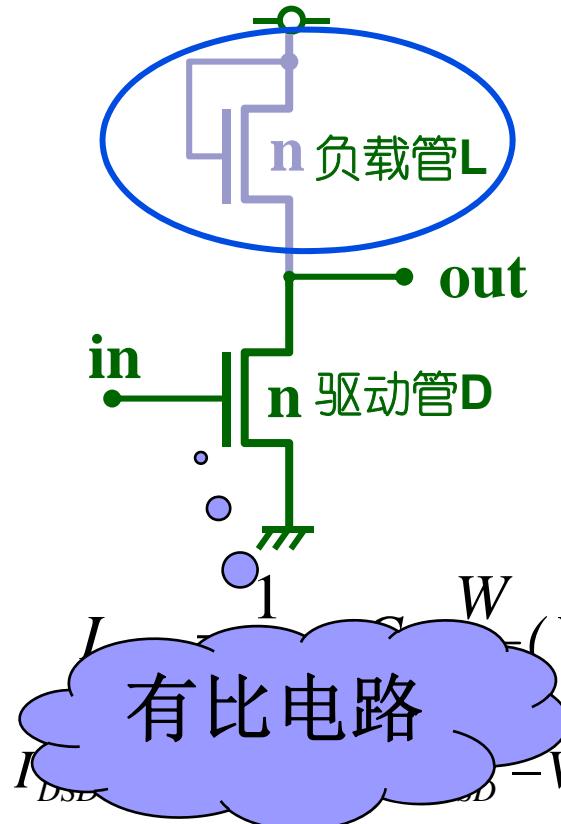
MOS晶体管的导通电阻随管子的尺寸不同而不同，通常在K欧数量级，假设它为3K欧，负载电阻取它的10倍为30K欧，用多晶硅作负载电阻时，如多晶硅的线宽为2微米的话

占面积很大，因此通常用MOS管做负载



反相器的几种实现方法

1. E/E MOS反相器（介绍饱和MOS负载反相器）



工作在饱和区

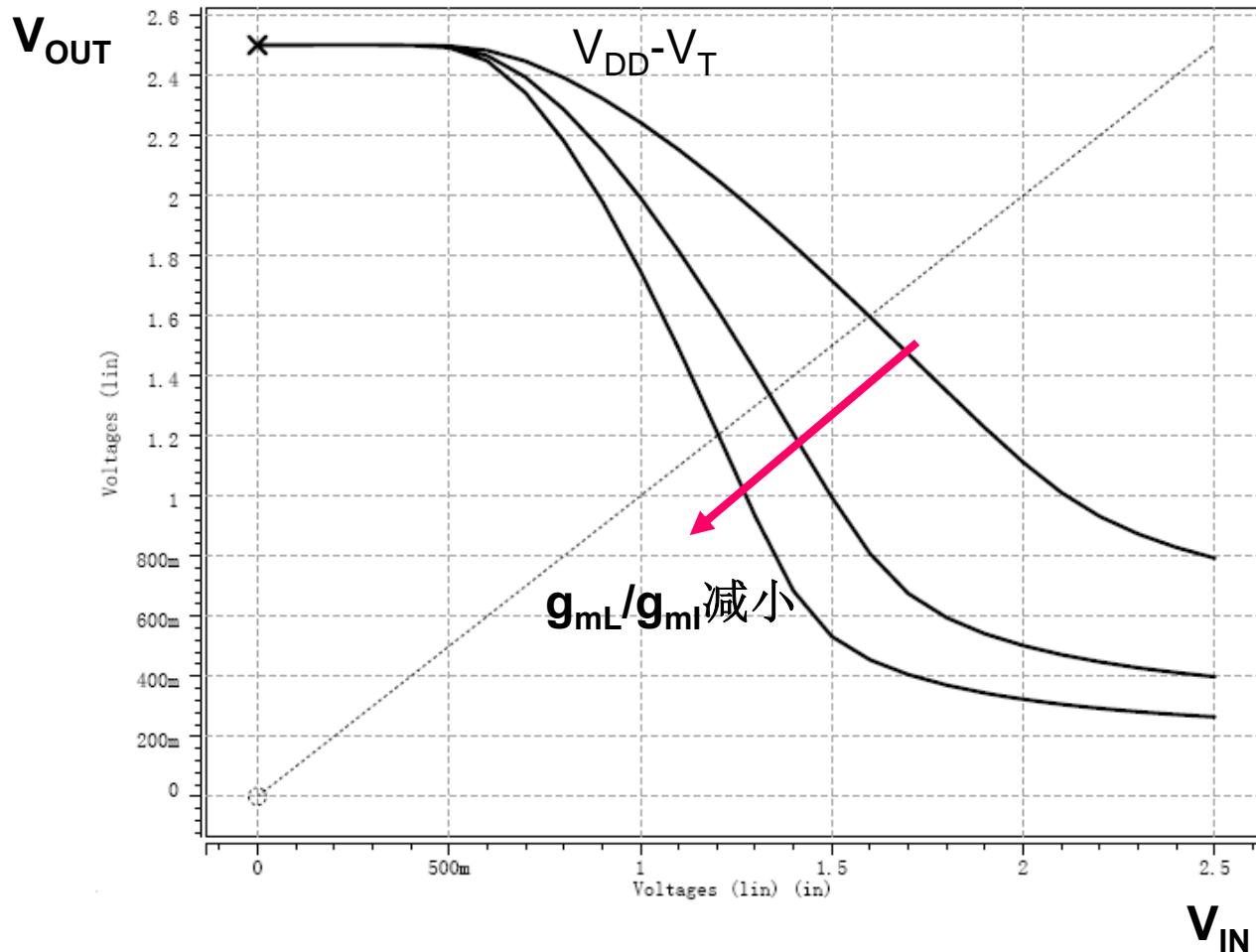
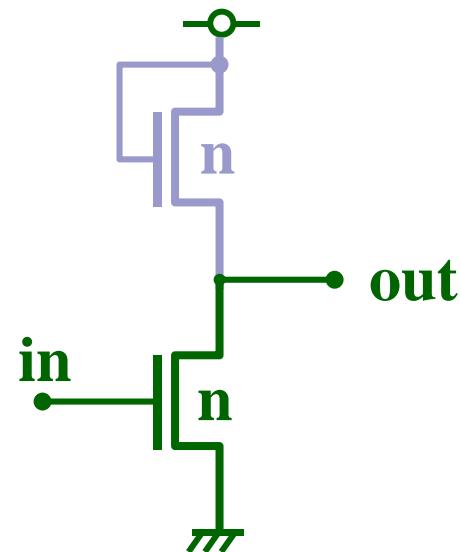
$$V_{ds} = V_{gs} > V_{gs} - V_{th}$$

$$V_{IN} \rightarrow 0 \quad V_{OH} = V_{DD} - V_{THL}$$

$$V_{OL} = \frac{1}{2} \frac{g_{mL}}{g_{mD}} (V_{DD} - V_{THL})^2$$

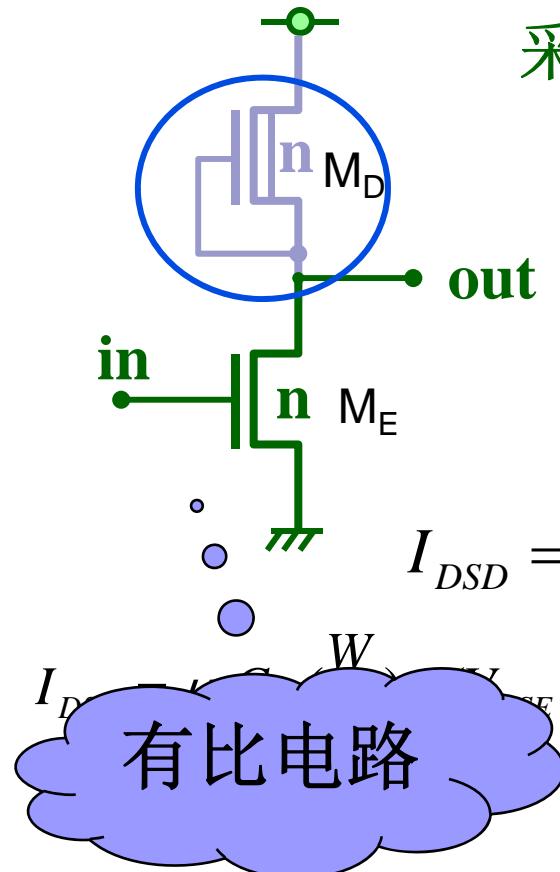
为使 V_{OL} 接近 0，要求 $g_{mL} \ll g_{mD}$

❖ E/E MOS反相器电压传输特性



反相器的几种实现方法

2. E/D MOS反相器



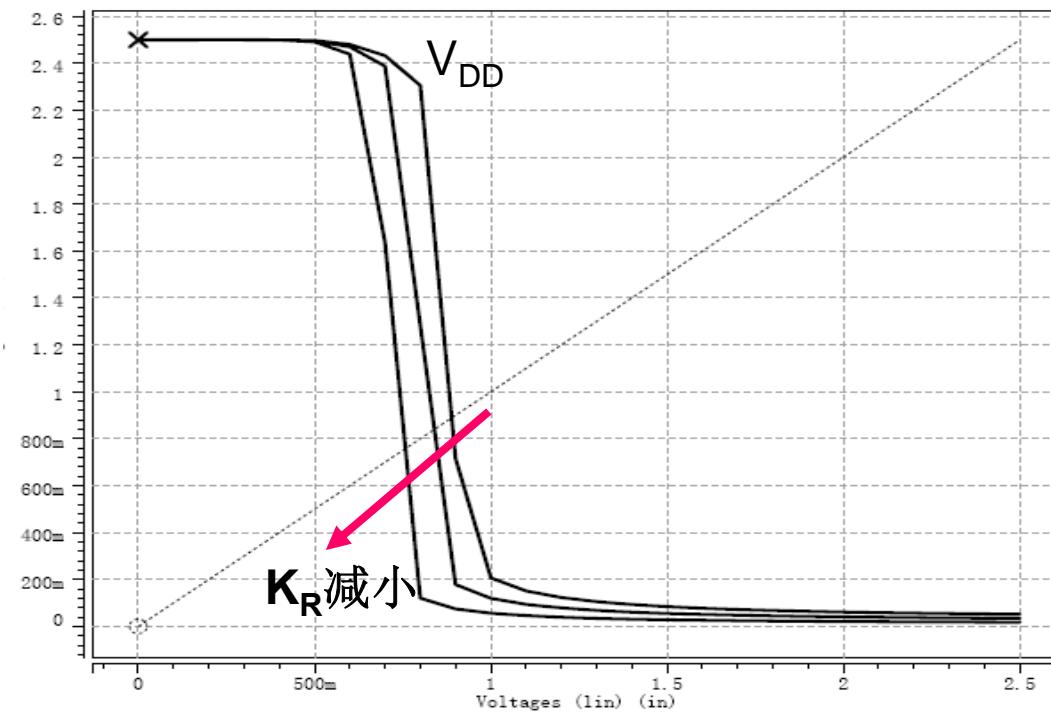
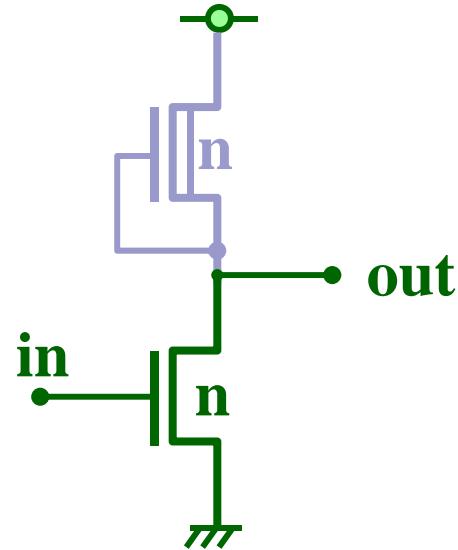
采用耗尽型, $V_{GS}=0$ 时,一直工作处于导通状态

$$V_{IN} \rightarrow 0 \text{ 驱 } V_{OH} \approx V_{DD}$$

$$V_{OL} \approx \frac{V_{TD}^2}{2K_R(V_{DD} - V_{TE})} \quad \begin{array}{l} \text{饱和导通} \\ \left(\frac{V_{TD}}{V_{DD} - V_{TE}} \right)^2 \end{array}$$
$$K_R = \frac{\mu_n C_{ox} \left(\frac{W}{L} \right)_E}{\mu_n C_{ox} \left(\frac{W}{L} \right)_D}$$

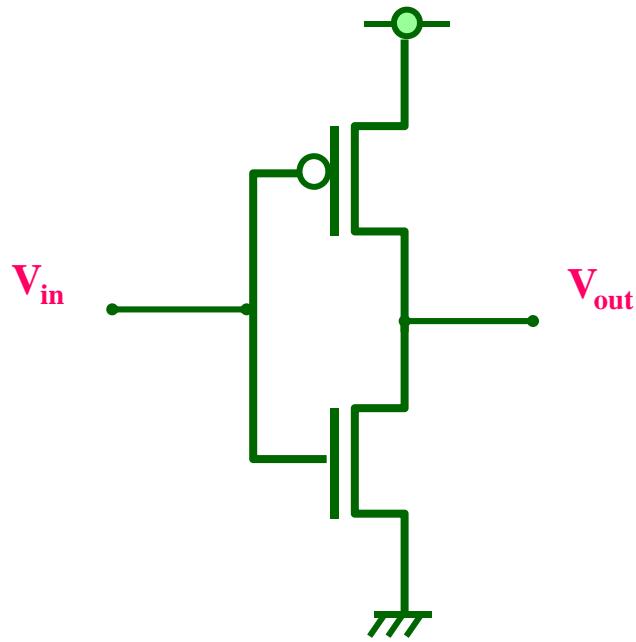
逻辑运算电路-反相器2

❖ E/D MOS反相器电压传输特性



反相器的几种实现方法

3. CMOS反相器



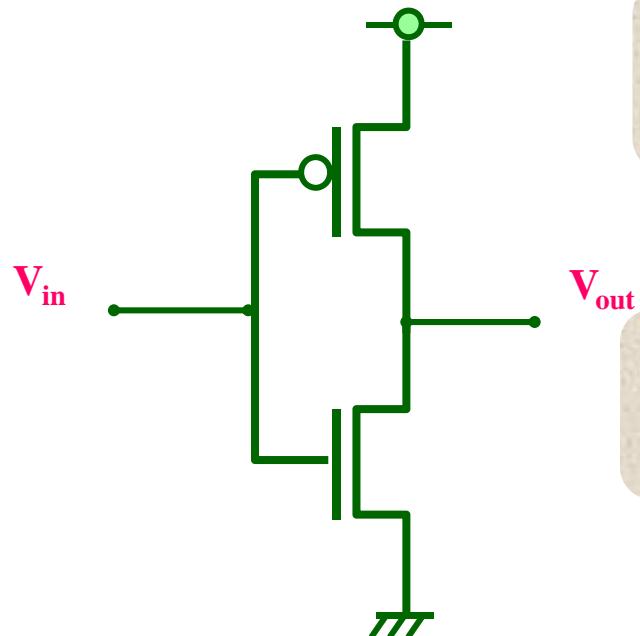
由PMOS和NMOS
所组成的互补型电路叫做
CMOS

C: complementary

CMOS电路的特点: **低功耗**

CMOS已成为现代集成电路特别是数字电路的主流

❖ CMOS反相器工作原理



当输入电压 V_{in} 为高电平时，PMOS截止，NMOS导通， $V_{out}=0$

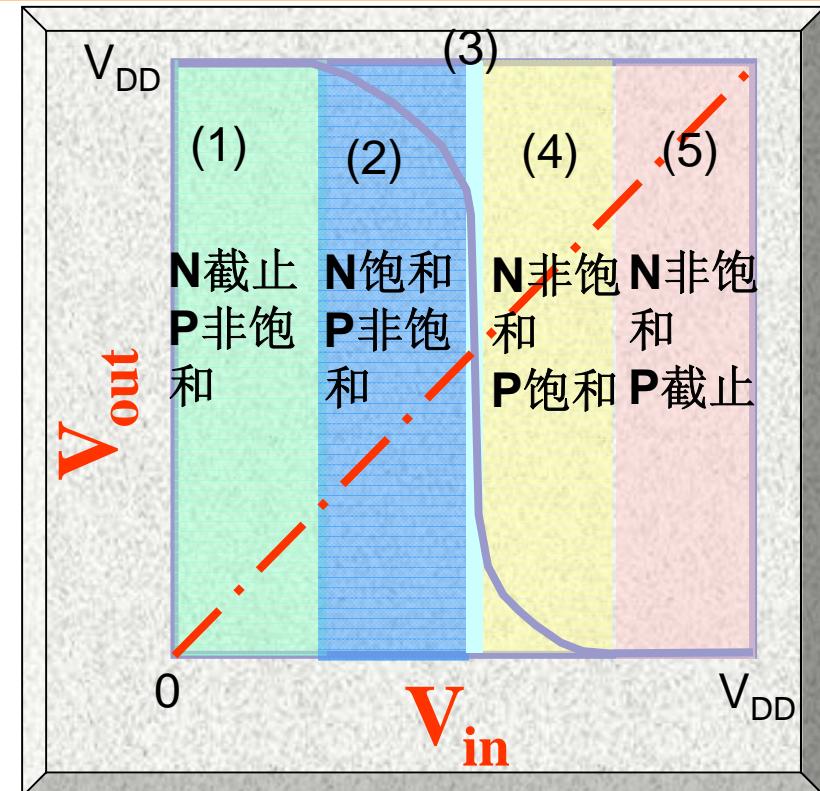
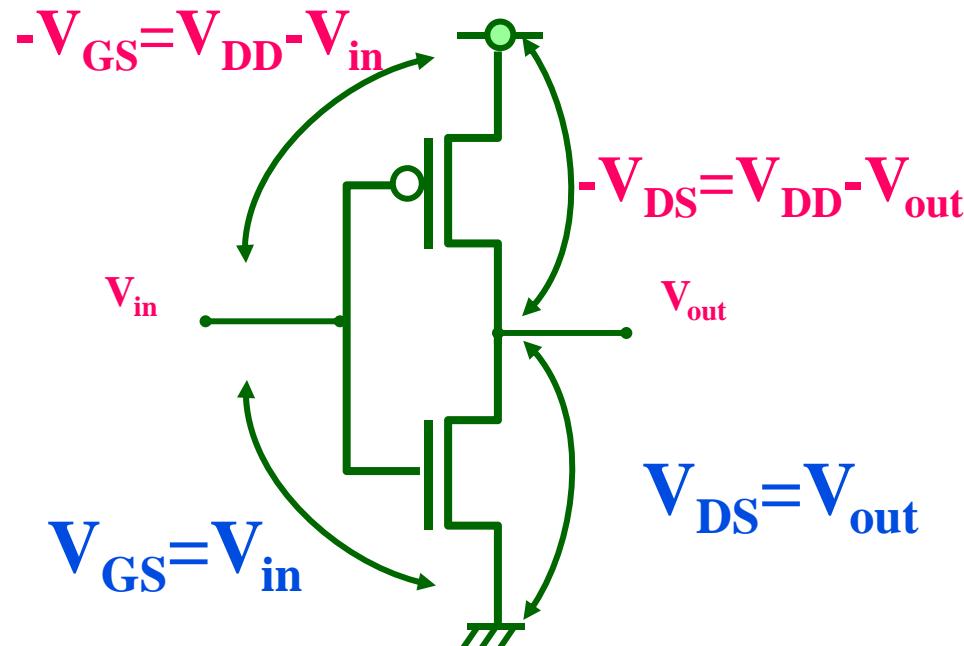
$$V_{OL}=0$$

当输入电压 V_{in} 为低电平时，PMOS导通，NMOS截止， $V_{out}=V_{DD}$

$$V_{OH}=V_{DD}$$

在输入为0或1(V_{DD})时，两个MOS管中总是一个截止一个导通，因此没有从 V_{DD} 到 V_{SS} 的直流通路，也没有电流流入栅极，因此其静态电流和功耗几乎为0。这是CMOS电路低功耗的主要原因。CMOS电路的最大特点之一是低功耗。

CMOS反相器的传输特性



NMOS

$$\begin{aligned}V_{in} &< V_{tn} \\V_{in} - V_{tn} &< V_{out} \\V_{in} - V_{tn} &> V_{out}\end{aligned}$$

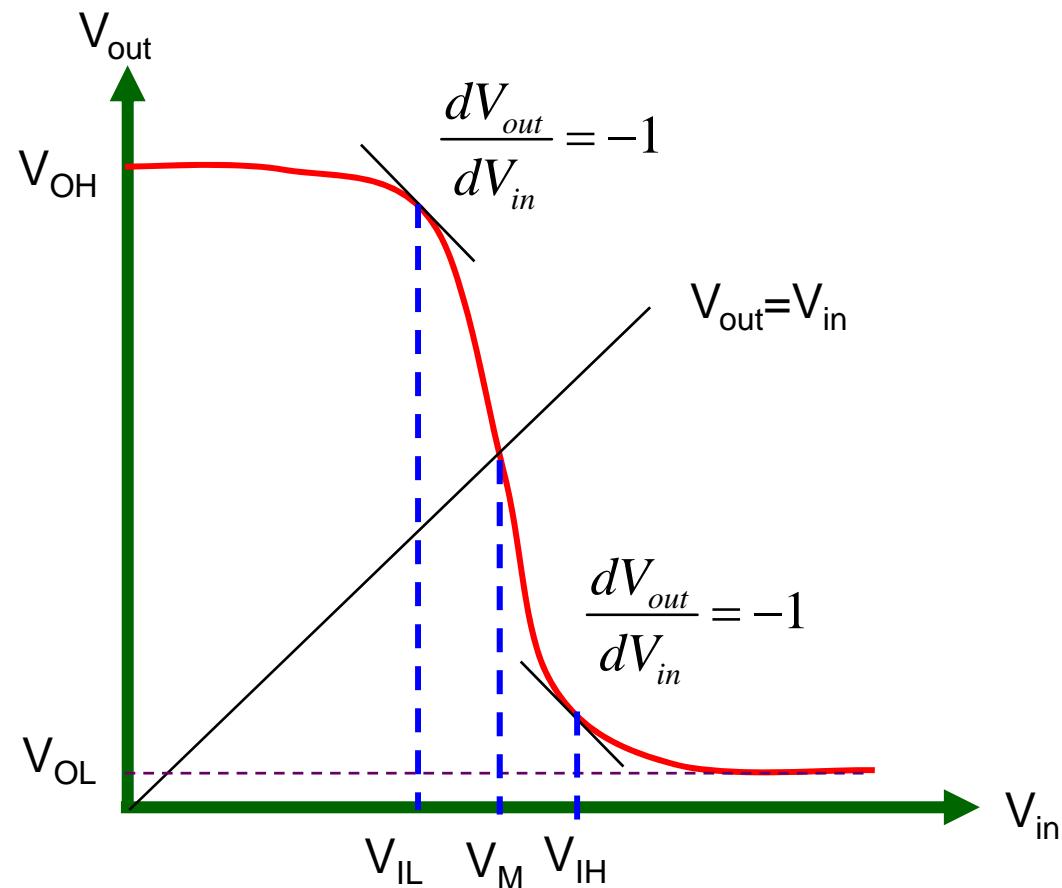
截止
饱和
非饱和

PMOS

$$\begin{aligned}(V_{DD} - V_{in}) &< -V_{tp} \\(V_{DD} - V_{in}) + V_{tp} &> V_{DD} - V_{out} \\(V_{DD} - V_{in}) + V_{tp} &< V_{DD} - V_{out}\end{aligned}$$

截止
非饱和
饱和

CMOS反相器的几个重要参数





1. V_{IL} 的计算

$$V_{IN} = V_{IL} \rightarrow \frac{dV_{out}}{dV_{in}} = -1$$

N管工作在饱和区, P管工作在线性区

$$K_P [2(V_{PD} - V_{in} - |V_{TP}|)(V_{DD} - V_{out}) - (V_{DD} - V_{out})^2] \\ = K_N (V_{in} - V_{TN})^2 \quad (1)$$

对 V_{in} 求导, 得

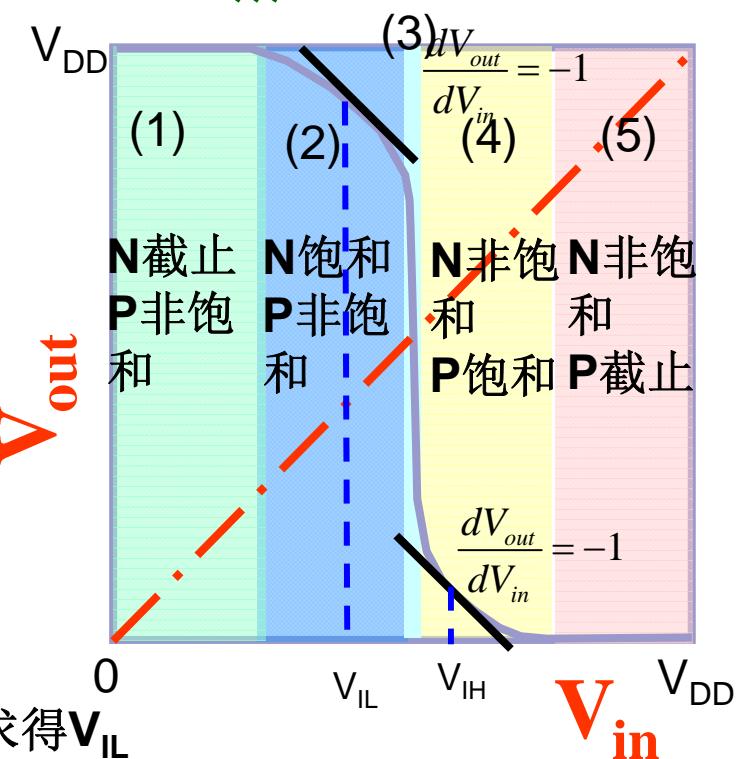
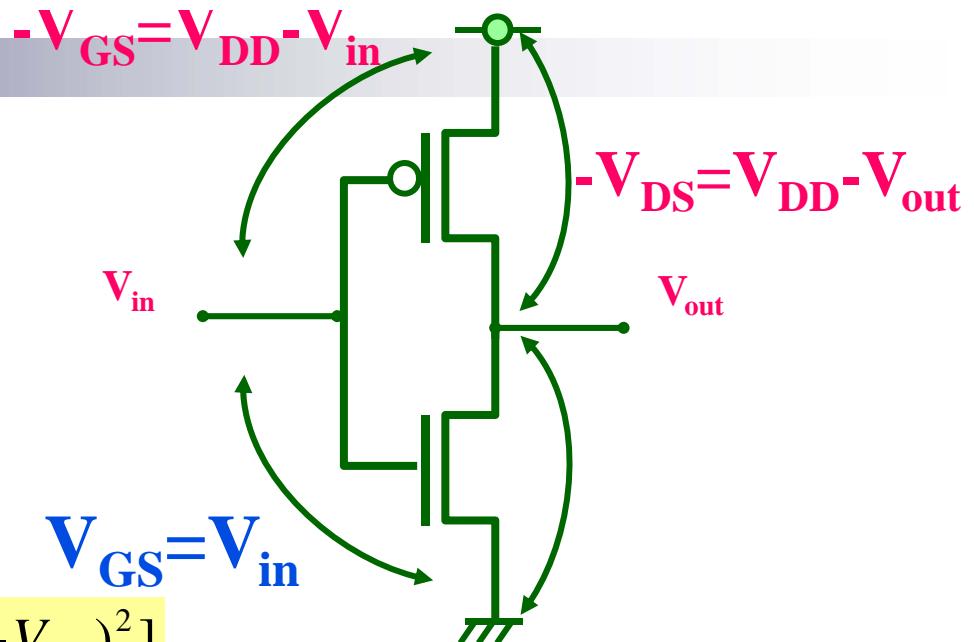
$$2K_N (V_{in} - V_{TN}) = 2K_P [(V_{DD} - V_{in} - |V_{TP}|)(-\frac{dV_{out}}{dV_{in}}) +$$

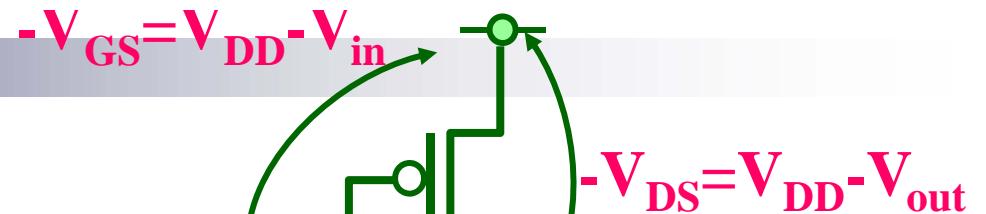
$$(V_{DD} - V_{out})(-1) - (V_{DD} - V_{out})(-\frac{dV_{out}}{dV_{in}})]$$

令 $\frac{dV_{out}}{dV_{in}} = -1$, 且 $V_{in} = V_{IL}$, 得

$$V_{IL} = \frac{2V_{out} + V_{TP} - V_{DD} + k_R V_{TN}}{1 + k_R} \quad (2)$$

由 (1) (2) 式联立可求得 V_{IL}





2. V_{IH} 的计算

$$V_{IN} = V_{IH} \rightarrow \frac{dV_{out}}{dV_{in}} = -1$$

N管工作在线性区, P管工作在饱和区

$$\begin{aligned} & K_N [2(V_{in} - V_{TN})V_{out} - V_{out}^2] \\ & = K_P (V_{DD} - V_{in} - |V_{TP}|)^2 \end{aligned} \quad (1)$$

对 V_{in} 求导, 得

$$2K_N [(V_{in} - V_{TN}) \left(\frac{dV_{out}}{dV_{in}} \right) + V_{out} - V_{out} \frac{dV_{out}}{dV_{in}}]$$

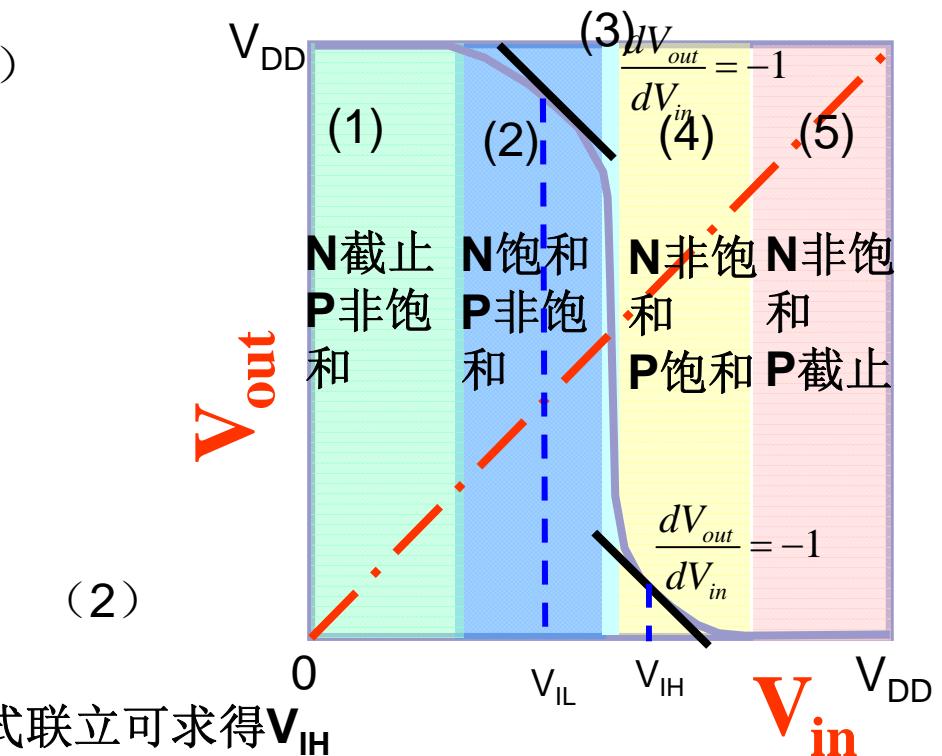
$$= 2K_P (V_{DD} - V_{in} - |V_{TP}|)$$

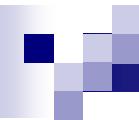
令 $\frac{dV_{out}}{dV_{in}} = -1$, 且 $V_{in} = V_{IH}$, 得

$$V_{IH} = \frac{V_{DD} + V_{TP} + k_R (2V_{out} + V_{TN})}{1 + k_R} \quad (2)$$

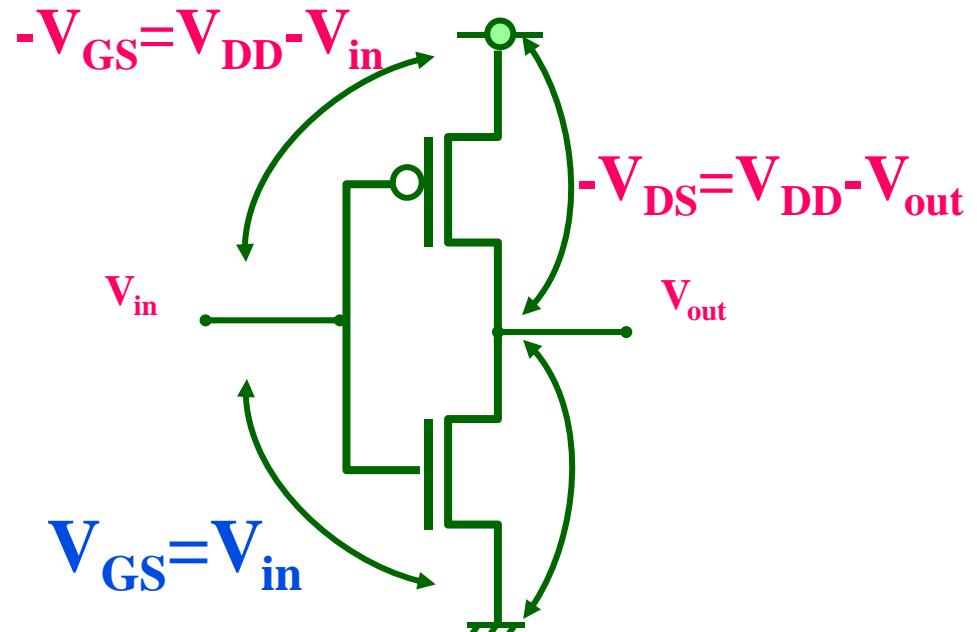
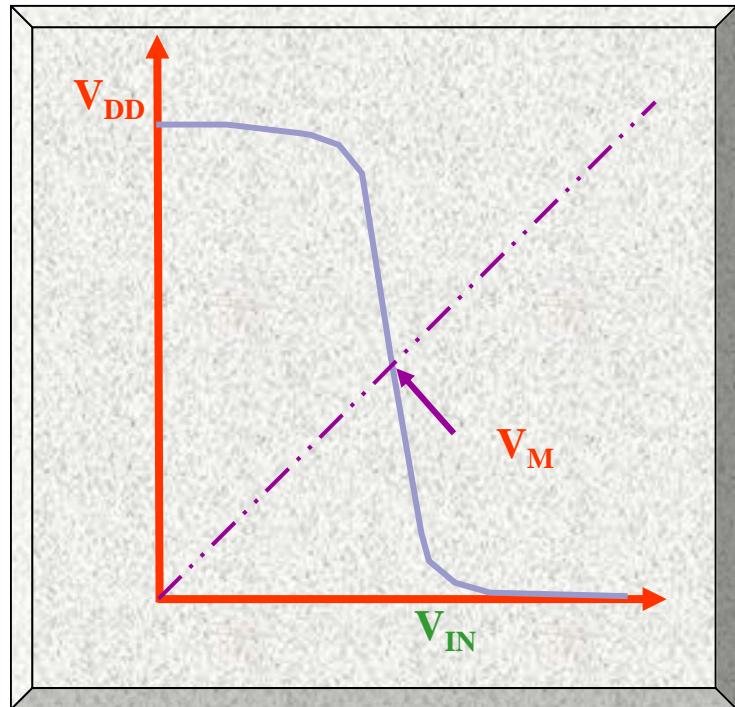
由 (1) (2) 式联立可求得 V_{IH}

2012/11/27





3. 逻辑阈值的计算

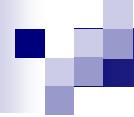


N管和P管均工作在饱和区

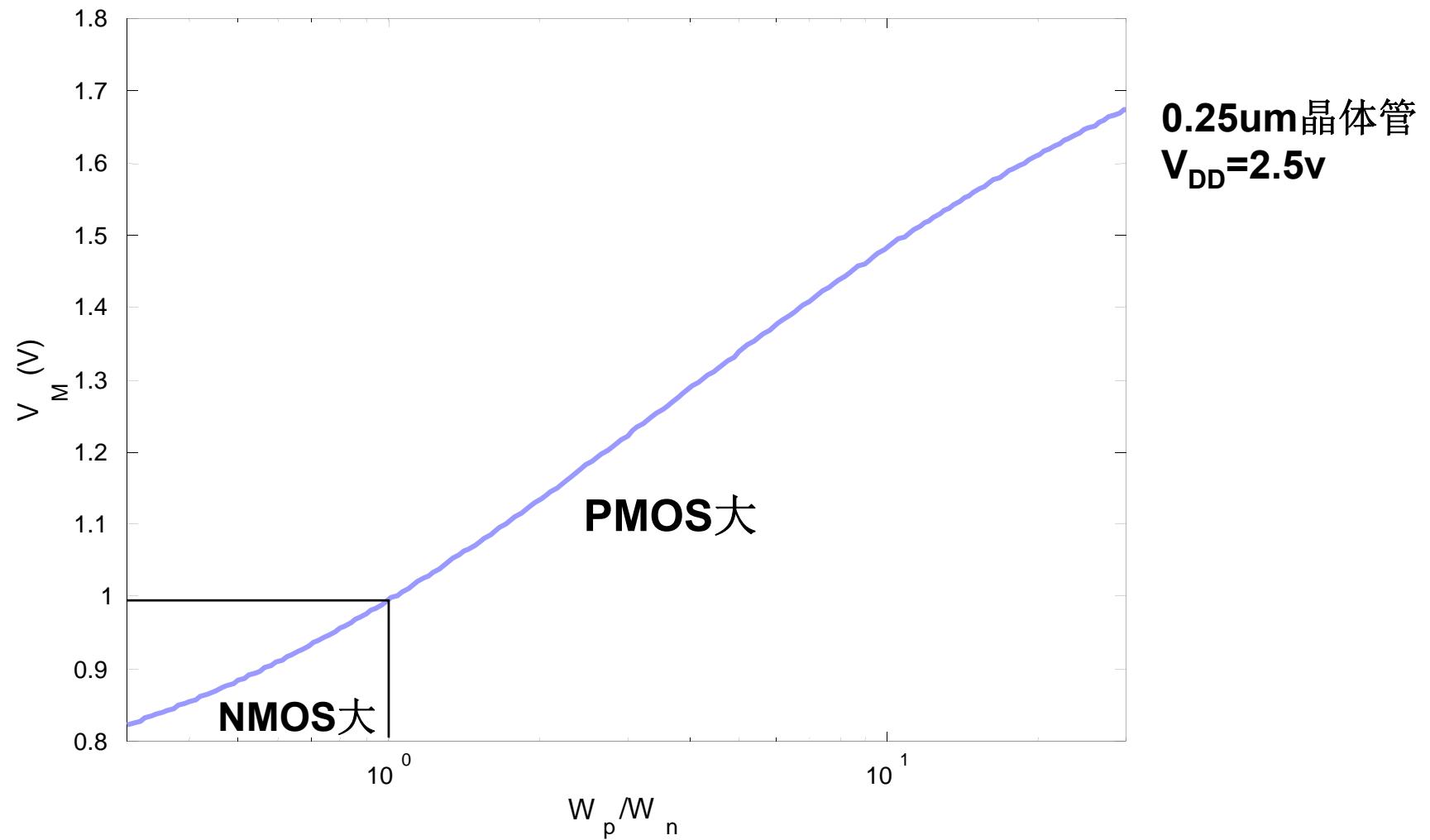
$$K_N(V_{in} - V_{TN})^2 = K_P(V_{DD} - V_{in} - |V_{TP}|)^2$$

令 $V_M = V_{in}$ 得

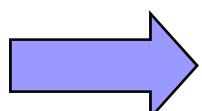
$$V_M = \frac{V_{DD} + V_{TP} + V_{TN} \sqrt{K_R}}{1 + \sqrt{K_R}}$$



逻辑阈值与晶体管尺寸的关系



CMOS反相器的噪声容限

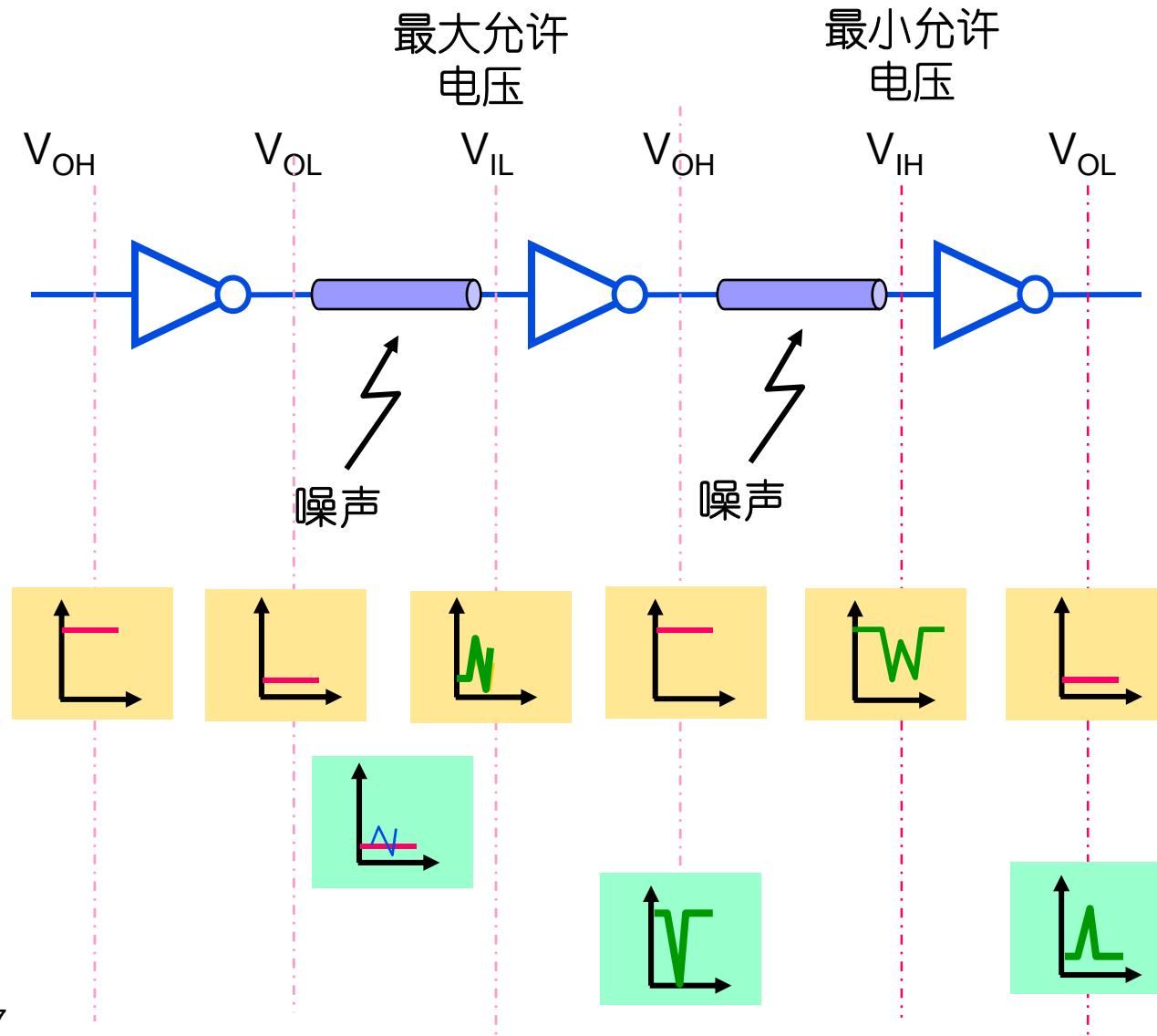
$$V_{IL} = \frac{2V_{out} + V_{TP} - V_{DD} + k_R V_{TN}}{1 + k_R}$$
$$V_{IH} = \frac{V_{DD} + V_{TP} + k_R (2V_{out} + V_{TN})}{1 + k_R}$$

$$NM_L = V_{IL} - V_{OL}$$
$$NM_H = V_{OH} - V_{IH}$$

例 考虑一个具有如下参数的CMOS反相器电路：

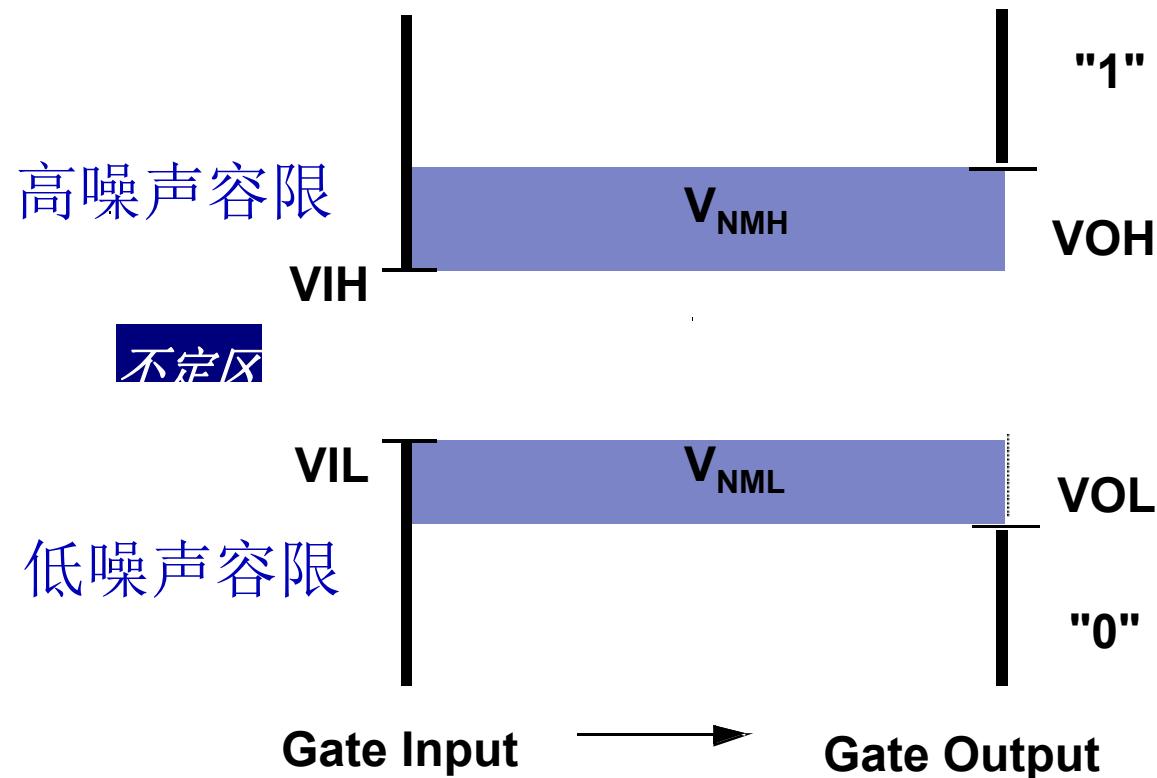
$$V_{DD} = 3.3V, V_{Tn} = 0.6V, V_{Tp} = -0.7V, K_n = 100\mu A/V^2, K_p = 40\mu A/V^2$$

计算电路的噪声容限

噪声抑制与噪声容限



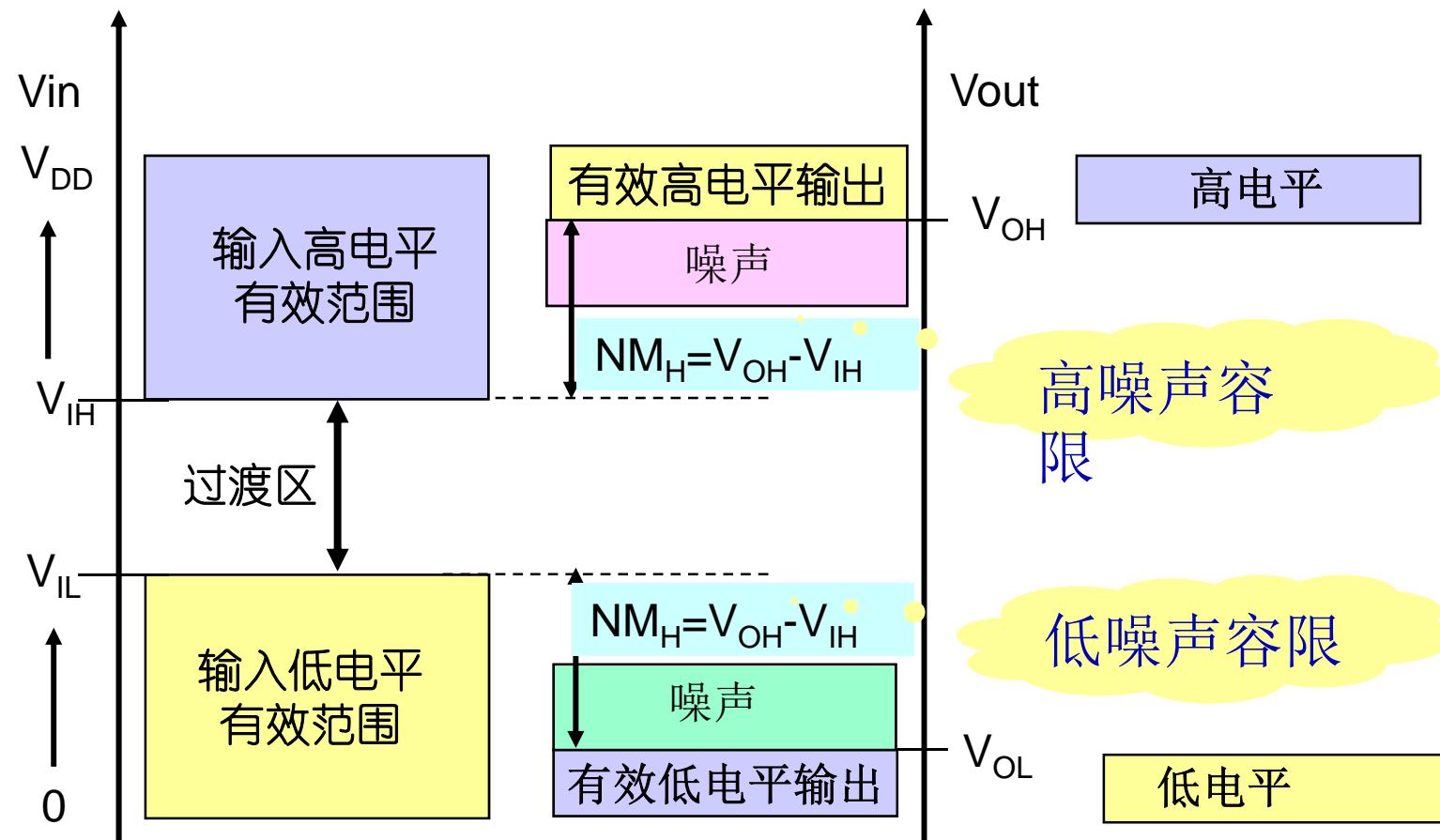
噪声抑制与噪声容限



$$V_{NML} = V_{IL} - V_{OL}$$

$$V_{NMH} = V_{OH} - V_{IH}$$

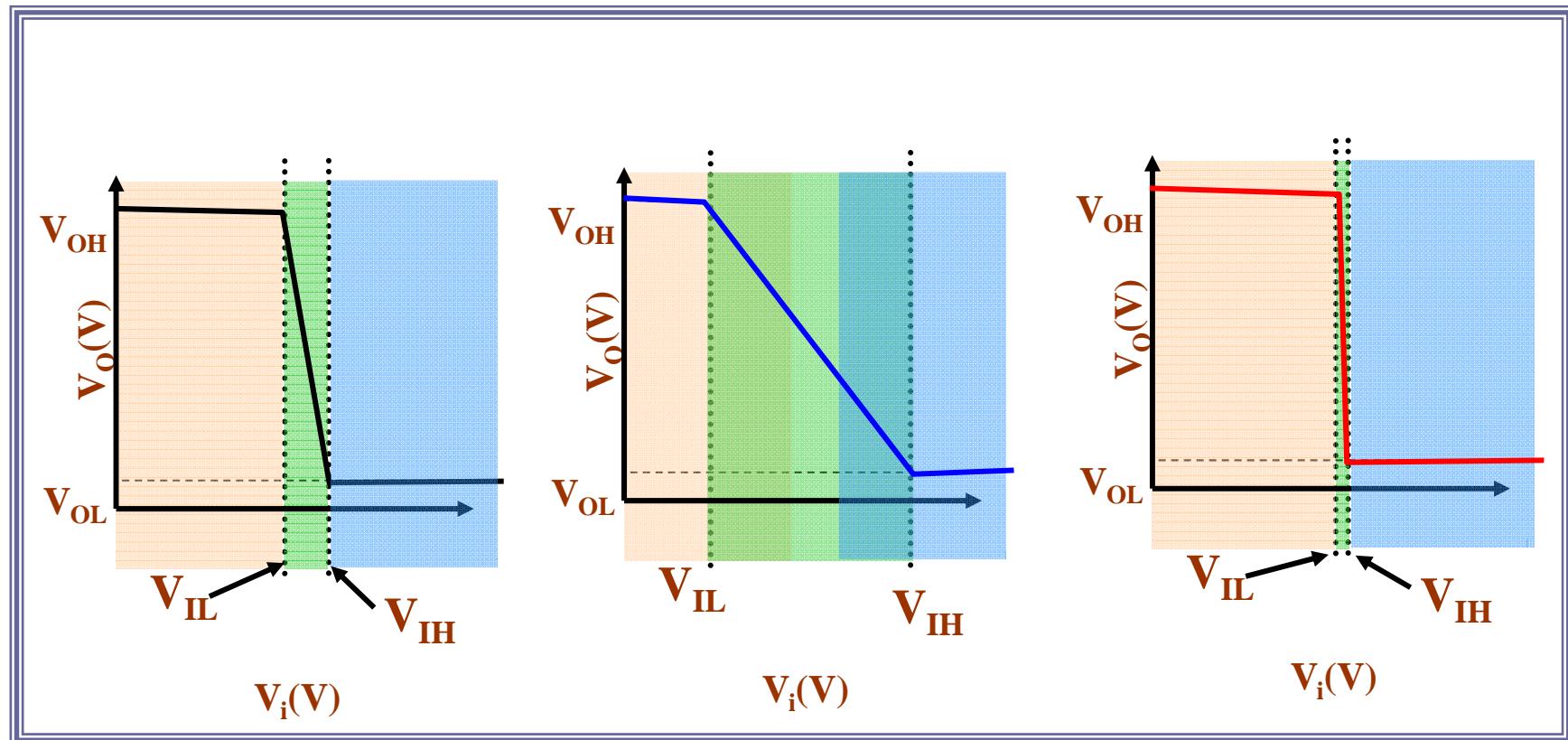
噪声抑制与噪声容限

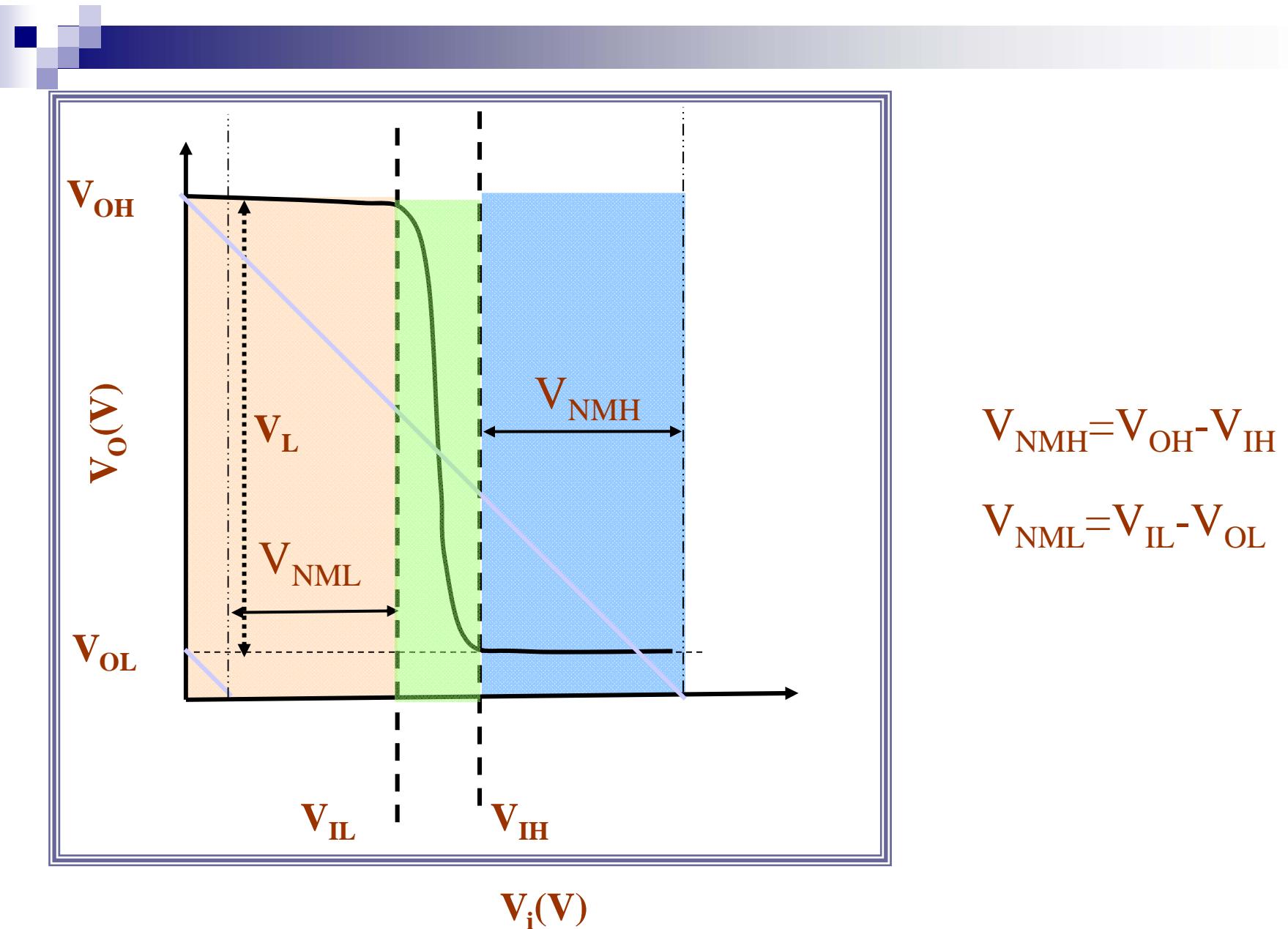


$$\text{噪声幅值} + V_{OL} < V_{IL} \longrightarrow \text{噪声幅值} < V_{IL} - V_{OL}$$

$$\text{噪声幅值} + V_{IH} < V_{OH} \longrightarrow \text{噪声幅值} < V_{OH} - V_{IH}$$

2. 抗干扰能力





$$V_{NMH} = V_{OH} - V_{IL}$$

$$V_{NML} = V_{IL} - V_{OL}$$

解：对于**CMOS**反相器来说， $V_{OL}=0V$, $V_{OH}=3.3V$

$$\begin{aligned} V_{IL} &= \frac{2V_{out} + V_{Tp} - V_{DD} + K_R V_{Tn}}{1 + K_R} \\ &= \frac{2V_{out} - 0.7 - 3.3 + 1.5}{1 + 2.5} = 0.57V_{out} - 0.71 \end{aligned}$$

当 $V_{IN}=V_{IL}$ 时，nMOS管工作在饱和区，pMOS管工作在线性区

则有： $K_P[2(V_{DD} - V_{in} - |V_{TP}|)(V_{DD} - V_{out}) - (V_{DD} - V_{out})^2] = K_N(V_{in} - V_{TN})^2$

$$40[2(3.3 - 0.57V_{out} + 0.71 - 0.7)(3.3 - V_{out}) - (3.3 - V_{out})^2] = 100(0.57V_{out} - 0.71 - 0.6)^2$$

$$0.66{V_{out}}^2 + 0.05V_{out} - 6.65 = 0$$

$$\begin{aligned} V_{out} &= \frac{-0.05 \pm \sqrt{0.05^2 + 4 \times 0.66 \times 6.65}}{2 \times 0.66} \\ &= \frac{-0.05 \pm 4.19}{2 \times 0.66} \end{aligned}$$

$$\begin{aligned} V_{out1} &= 3.14V \\ V_{out2} &= -3.17V \end{aligned} \quad \therefore \quad V_{out} = 3.14V$$

$$V_{IL} = 0.57V_{out} - 0.71 = 1.08V$$

$$\begin{aligned}
 V_{IH} &= \frac{V_{DD} + V_{Tp} + K_R(2V_{out} + V_{Tn})}{1 + K_R} \\
 &= \frac{3.3 - 0.7 + 2.5(2V_{out} + 0.6)}{1 + 2.5} = 1.43V_{out} + 1.17
 \end{aligned}$$

当 $V_{IN}=V_{IH}$ 时,nMOS管工作在线性区,pMOS管工作在饱和区

$$\begin{aligned}
 \text{则有: } K_N[2(V_{in} - V_{TN})V_{out} - V_{out}^2] &= K_P(V_{DD} - V_{in} - |V_{TP}|)^2 \\
 100[2(1.43V_{out} + 1.17 - 0.6)V_{out} - V_{out}^2] &= 40(3.3 - 1.43V_{out} - 1.17 - 0.7)^2
 \end{aligned}$$

$$100[2(1.43V_{out} + 1.17 - 0.6)V_{out} - V_{out}^2] = 40(3.3 - 1.43V_{out} - 1.17 - 0.7)^2$$

$$2.61V_{out}^2 + 6.94V_{out} - 2.04 = 0$$

$$V_{out} = \frac{-6.94 \pm \sqrt{6.94^2 + 4 \times 2.61 \times 2.04}}{2 \times 2.61}$$

$$V_{out1} = 0.27\text{V}$$

$$\therefore V_{out} = 0.27\text{V}$$

$$V_{out2} = -2.93\text{V}$$

$$V_{IH} = 1.43V_{out} + 1.17 = 1.55\text{V}$$

$$NM_L = V_{IL} - V_{OL} = 1.08\text{V}$$

$$NM_H = V_{OH} - V_{IH} = 3.3 - 1.55 = 1.75\text{V}$$